Eiji Kusano

List of Publications by Year
in descending order

65	772	430874	526287
papers	citations	18 h-index	27 g-index

66	66	66	693
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Growth of flat-topped, mound-shaped grains with voids when depositing silver thin films at high substrate temperatures using direct-current magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	2.1	2
2	Discharge characteristics of electronegative Mgâ€“CF4 direct current magnetron sputtering by probe measurements. Journal of Applied Physics, 2021, 129, .	2.5	1
3	Homologous substrate-temperature dependence of structure and properties of TiO2, ZrO2, and HfO2 thin films deposited by reactive sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	2.1	5
4	Deposition of Organic Thin Films by Magnetron Sputtering. Journal of the Adhesion Society of Japan, 2019, 55, 394-403.	0.0	0
5	Revisitation of the structure zone model based on the investigation of the structure and properties of Ti, Zr, and Hf thin films deposited at 70â€“600â€‰Â°C using DC magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, 041506.	2.1	9
6	Radio frequency sputter deposition of Cu2ZnSnS4 thin films with a temperature-controlled reflector wall: Effects of H2 addition to the sputtering gas. Thin Solid Films, 2018, 646, 75-82.	1.8	2
7	Mechanisms of the structural modification of Ti films by pulsed direct current and inductively coupled plasma-assisted pulsed direct current sputtering. Thin Solid Films, 2017, 634, 73-84.	1.8	3
8	Kagayuzen Glass Panel Fabricated by Using Glass Laminating Technology. Hyomen Kagaku, 2017, 38, 425-426.	0.0	0
9	Control of composition and properties by the use of reflector wall in RF sputter deposition of Cu2ZnSnS4 thin films. Thin Solid Films, 2015, 589, 433-440.	1.8	6
10	Preface (TACT 2011 Special Issue). Thin Solid Films, 2013, 529, 1.	1.8	0
11	Structure modification of titanium oxide thin films by rf-plasma assistance in Tiâ€“O2 reactive dc and pulsed dc sputtering. Thin Solid Films, 2013, 531, 49-55.	1.8	4
12	Interface stress induced hardness enhancement and superelasticity in polytetrafluoroethylene/metal multilayer thin films. Thin Solid Films, 2011, 520, 404-412.	1.8	13
13	ISSP 2009 Special Issue Preface. Thin Solid Films, 2010, 518, S1.	1.8	0
14	Removal of Ion-Implanted Photoresists Using Atomic Hydrogen. Journal of the Electrochemical Society, 2010, 157, H361.	2.9	35
15	Effects of radio-frequency plasma on structure and properties in Ti film deposition by dc and pulsed dc magnetron sputtering. Thin Solid Films, 2009, 517, 5837-5843.	1.8	25
16	Growth of carbon with vertically aligned nanoscale flake structure in capacitively coupled rf glow discharge. Vacuum, 2008, 82, 754-759.	3.5	17
17	Characterization of organic polymer thin films deposited by rf magnetron sputtering. Vacuum, 2008, 83, 564-568.	3.5	18
18	Standing-wave Effect in Photoresist with and without HMDS. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2008, 21, 299-304.	0.3	6

#	Article	IF	Citations
19	Resist Removal by using Atomic Hydrogen. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2008, 21, 293-298.	0.3	36
20	é«˜å“æ³¢ãƒ—ãƒ©ã‚ºãƒžæ”¯æ´ã‚¹ãƒ'ãƒƒã‚¿ãƒªãƒ³ã‚°æ³•ã«ã‚ˆã‚‹ Ti è–„è†œã®æ§‹é€ ãŠã‚ˆã³ç‰©æ€§åˆ¶å¾¡. Journal of the Vacuum Soci	0.2	0
21	ã‚¹ãƒ'ãƒƒã‚¿ãƒªãƒ³ã‚°æ³•è†œã«ãŠã'ã‚‹è–„è†œæ§‹é€ åˆ¶å¾¡. Shinku/Journal of the Vacuum Society of Japan, 2007, 50, 215-21.	0.2	14
22	Mechanisms of carrier generation and transport in Ni-doped Cu2O. Vacuum, 2006, 80, 756-760.	3.5	23
23	Compatibility of Lithium Oxide Single Crystals with Tungsten Sputtered Films-The Effect of Passivation Films-. Funtai Oyobi Fummatsu Yakin/Journal of the Japan Society of Powder and Powder Metallurgy, 2005, 52, 427-429.	0.2	1
24	Formation of Carbon Nano-flakes by RF Magnetron Sputtering Method. Shinku/Journal of the Vacuum Society of Japan, 2004, 47, 82-86.	0.2	9
25	Polyimide-based organic thin films prepared by rf magnetron sputtering. Thin Solid Films, 2003, 433, 274-276.	1.8	6
26	Historical Transition in Sputtering Method. Shinku/Journal of the Vacuum Society of Japan, 2003, 46, 719-725.	0.2	0
27	OS04W0318 Residual stress measurements on Cu thin films with various thicknesses using synchrotron radiation. The Abstracts of ATEM International Conference on Advanced Technology in Experimental Mechanics Asian Conference on Experimental Mechanics, 2003, 2003.2, _OS04W0318-_OS04W0318.	0.0	0
28	Preparation of amorphous Si1â^'xCx (0â‰xâ‰1) films by alternate deposition of Si and C thin layers using a dual magnetron sputtering source. Surface and Coatings Technology, 2002, 149, 76-81.	4.8	11
29	Electrical and mechanical properties of SnO2:Nb films for touch screens. Vacuum, 2002, 66, 365-371.	3.5	68
30	Effects of Interfacial Energy on Internal Stress and Hardness in Polytetrafluoroethylene/Metal System Multilayered Films.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 223-226.	0.2	0
31	Imidized organic thin films deposited on glass substrates. Thin Solid Films, 2001, 392, 254-257.	1.8	17
32	Effects of excess oxygen introduced during sputter deposition on carrier mobility in as-deposited and postannealed indiumâ€"tinâ€"oxide films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2001, 19, 1636-1641.	2.1	15
33	Energetic Analysis of Al/TiN Multilayered Films by Nano-indentation.. Shinku/Journal of the Vacuum Society of Japan, 2001, 44, 100-104.	0.2	0
34	Phonon scattering in electron transport phenomena of ITO films. Vacuum, 2000, 59, 492-499.	3.5	36
35	A smart gas sensor using polymer-film-coated quartz resonator microbalance. Sensors and Actuators B: Chemical, 2000, 66, 16-18.	7.8	38
36	Elastic and plastic energies in sputtered multilayered Tiâ€"TiN films estimated by nanoindentation. Surface and Coatings Technology, 2000, 126, 131-135.	4.8	32

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37	Time-dependent O2 mass balance change and target surface oxidation during mode transition in Tiâ€“O2 reactive sputtering. Journal of Applied Physics, 2000, 87, 2015-2019.	2.5	21
38	Dependence of Ar+ and Ti+ Ion Energy Distribution on dc Self Bias of the rf Inductive Coil in Inductively-coupled rf Plasma Enhanced Magnetron Sputtering.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 409-412.	0.2	0
39	Dependence of Ar+ and Ti+ Ion Energy Distributions on Ar Pressure in Inductively Coupled rf Plasma Enhanced Magnetron Sputtering.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 413-416.	0.2	0
40	Ion energy distribution in ionized dc sputtering measured by an energy-resolved mass spectrometer. Vacuum, 1999, 53, 21-24.	3.5	20
41	Preparation of TiC films by alternate deposition of Ti and C layers using a dual magnetron sputtering source. Surface and Coatings Technology, 1999, 120-121, 378-382.	4.8	24
42	Effects of Ar pressure on ion flux energy distribution and ion fraction in r.f.-plasma-assisted magnetron sputtering. Surface and Coatings Technology, 1999, 120-121, 189-193.	4.8	18
43	Hardness of compositionally nano-modulated TiN films. Scripta Materialia, 1999, 12, 807-810.	0.5	11
44	Energy Dissipation in Al/TiN Double Layered Films by Nano-indentation.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 652-656.	0.2	2
45	Hardness and Adhesion Strength Enhancement by Compositional Gradient Structure and Optimization of Ar Partial Pressure for ZrN/Zr/ZrO2 and ZrN/ZrO2 Films Deposited by Reactive Sputtering.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 167-170.	0.2	0
46	Participation of Phonon Scattering in ITO Films.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 179-182.	0.2	0
47	TiC Film Preparation by Alternate Deposition of Ti and C with Dual Magnetron Sputtering Method.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 384-387.	0.2	0
48	Study of Corona-Glow Discharge Transition Using Q-V Lissajous' and Dust-Figure Methods.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 396-400.	0.2	1
49	Dependence of Ar+ and Ti+ Ion Energy Distribution on Cathode Current in Magnetron Sputtering Enhanced by Additional Plasma.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 405-408.	0.2	0
50	Hardening Mechanism of Compositionally Modulated Ti-TiN Multilayer Films.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 657-662.	0.2	0
51	Evaluation of adhesion strength of Ti films on Si(100) by the internal stress method. Thin Solid Films, 1998, 317, 165-168.	1.8	37
52	Adhesion and hardness of compositionally gradient TiO2/Ti/TiN, ZrO2/Zr/ZrN, and TiO2/Ti/Zr/ZrN coatings. Thin Solid Films, 1998, 334, 151-155.	1.8	20
53	New photostimulable phosphor materials for an imaging plate of computed radiography. , 1998, , .		2
54	Energy distribution of particles generated by magnetron sputtering enhanced additional rf plasma.. Shinku/Journal of the Vacuum Society of Japan, 1998, 41, 155-158.	0.2	1

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55	Adhesion and Hardness of Compositionally Gradient.. Shinku/Journal of the Vacuum Society of Japan, 1998, 41, 111-114.	0.2	0
56	Nano-indentation Hardness of Compositionally Modulated Ti-TiN Multilayer Films.. Shinku/Journal of the Vacuum Society of Japan, 1998, 41, 115-118.	0.2	1
57	TiC Film Preparation by a Solid Source Reactive Sputtering Method.. Shinku/Journal of the Vacuum Society of Japan, 1998, 41, 520-523.	0.2	0
58	Smart photostimulable phosphor materials for erasable and rewritable optical memory. , 1997, , .		1
59	Nanoindentation Hardness of Compositionally Modulated Ti/TiN Multilayered Films. Materials Research Society Symposia Proceedings, 1997, 505, 577.	0.1	5
60	Formation of compositionally graded multilayer films by discharge gas flow modulation in magnetron sputtering. Journal of Non-Crystalline Solids, 1997, 218, 58-61.	3.1	6
61	Vanadium reactive magnetron sputtering in mixed Ar/O2 discharges. Thin Solid Films, 1997, 298, 122-129.	1.8	26
62	Modeling of timeâ€dependent process changes and hysteresis in Tiâ€O2reactive sputtering. Journal of Applied Physics, 1993, 73, 8565-8574.	2.5	18
63	An investigation of hysteresis effects as a function of pumping speed, sputtering current, and O2/Ar ratio, in Tiâ€O2reactive sputtering processes. Journal of Applied Physics, 1991, 70, 7089-7096.	2.5	35
64	Time-dependent simulation modelling of reactivesputtering. Thin Solid Films, 1990, 193-194, 84-91.	1.8	16
65	Effects of microstructure and nonstoichiometry on electrical properties of vanadium dioxide films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1989, 7, 1314-1317.	2.1	55